

REMARKS

By this amendment claims 1, 13, and 25-26 have been amended. Accordingly, claims 1-26 and 29 are currently pending in the application, of which claims 1, 13, and 25-26 are independent claims.

Applicants respectfully submit that the above amendments do not add new matter to the application and are fully supported by the specification. Support for the amendments may be found at least in Figures 2-3.

In view of the above amendments and following Remarks, Applicants respectfully request reconsideration and timely withdrawal of the pending rejections for the reasons discussed below.

Rejections Under 35 U.S.C. § 103

Claims 1, 2, 4, 5, and 8-11 stand rejected under 35 U.S.C. § 103(a) as being allegedly unpatentable over U. S. Patent No. 5,652,067 issued to Ito, *et al.* ("Ito"). Applicants respectfully traverse this rejection for at least the following reasons.

To establish a *prima facie* case of obviousness, three basic criteria must be met. First, there must be some suggestion or motivation to modify the reference or to combine reference teachings. Second, there must be a reasonable expectation of success. Third, the reference or references, when combined, must disclose or suggest all of the claim limitations. The motivation to modify the prior art and the reasonable expectation of success must both be found in the prior art and not based upon a patent applicant's disclosure. See *in re Vaeck*, 947 F.2d 488, 20 USPQ2d 1438 (Fed. Cir. 1991).

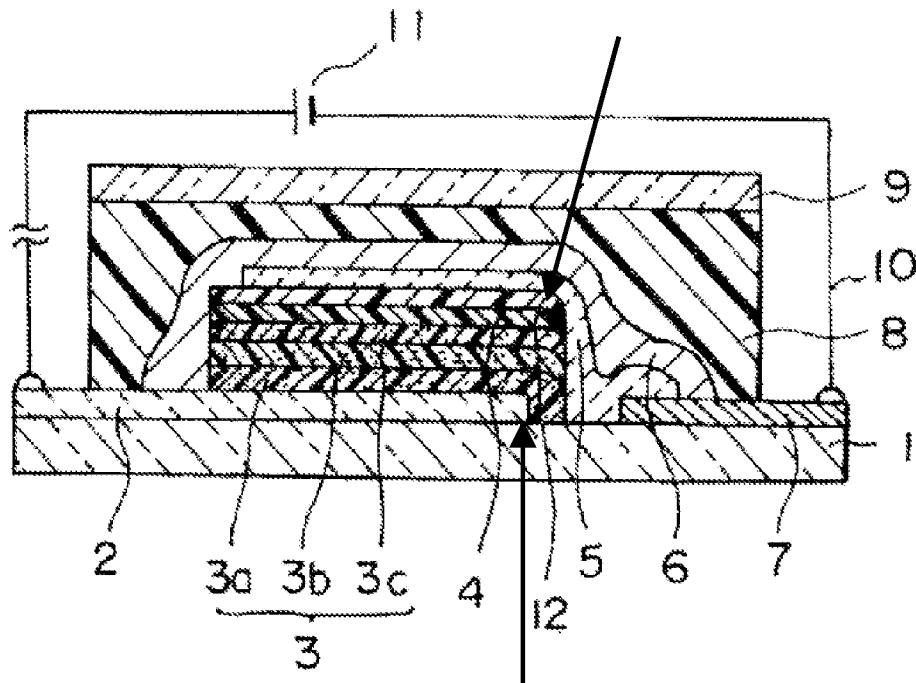
Assuming *arguendo* that the reference may be modified and a reasonable expectation of success exists, the reference does not disclose or suggest all of the claim limitations.

Amended claim 1 recites *inter alia*:

"...wherein the electron injecting layer is formed using a shadow mask such that the electron injecting layer overlaps the emissive layer without extending over the first and the second ends of the anode layer and the emissive layer" (emphasis added)

As seen in the figure below, Ito shows that the EITL (12) or the electron injecting layer overlaps and extends over an end of the anode layer (2). Therefore, Ito fails to teach or suggest every limitation of amended claim 1.

FIG.9



Accordingly, Applicants respectfully request withdrawal of the 35 U.S.C. § 103(a) rejection of claim 1. Claims 2-12 depend from claim 1 and are allowable at least for this reason. Since none of the other prior art of record, whether taken alone or in any combination, discloses or suggests all the features of the claimed invention, Applicants respectfully submit that independent claim 1, and all the claims that depend therefrom, are allowable.

Claims 13, 14, 16, 17, and 20-23 stand rejected under 35 U.S.C. § 103(a) as being allegedly unpatentable over U. S. Patent No. 5,652,067 issued to Ito, *et al.* ("Ito"). Applicants respectfully traverse this rejection for at least the following reasons.

Amended claim 13 recites *inter alia*:

"...wherein the electron injecting layer is formed using a shadow mask such that the electron injecting layer overlaps the emissive layer without extending over the first and the second ends of the anode layer and the emissive layer" (emphasis added)

As noted above with regard to claim 1, Ito fails to teach or suggest such features.

Accordingly, Applicants respectfully request withdrawal of the 35 U.S.C. § 103(a) rejection of claim 13. Claims 14-24 depend from claim 13 and are allowable at least for this reason. Since none of the other prior art of record, whether taken alone or in any combination, discloses or suggests all the features of the claimed invention, Applicants respectfully submit that independent claim 13, and all the claims that depend therefrom, are allowable.

Claims 12 and 24 stand rejected under 35 U.S.C. § 103(a) as being allegedly unpatentable over U. S. Patent No. 5,652,067 issued to Ito, *et al.* ("Ito") in view of Japanese Patent No. 09-082476 issued to Kaneko, *et al.* ("Kaneko"). Applicants respectfully traverse this rejection for at least the following reasons.

As noted above, Ito fails to teach or suggest the claimed features of claims 1 and 13. Kaneko fails to cure the deficiencies of Ito. Claims 12 and 24 depend from claims 1 and 13 and are allowable at least for this reason.

Accordingly, Applicants respectfully request withdrawal of the 35 U.S.C. § 103(a) rejection of claims 12 and 24. Since none of the other prior art of record, whether taken alone or in any combination, discloses or suggests all the features of the claimed invention, Applicants respectfully submit that claims 12 and 24 are allowable.

Claims 3 and 15 stand rejected under 35 U.S.C. § 103(a) as being allegedly unpatentable over U. S. Patent No. 5,652,067 issued to Ito, *et al.* ("Ito") in view of U.S. Patent No. 5,837,391 issued to Utsugi, *et al.* ("Utsugi"). Applicants respectfully traverse this rejection for at least the following reasons.

As noted above, Ito fails to teach or suggest the claimed features of claims 1 and 13. Utsugi fails to cure the deficiencies of Ito. Claims 3 and 15 depend from claims 1 and 13 and are allowable at least for this reason.

Accordingly, Applicants respectfully request withdrawal of the 35 U.S.C. § 103(a) rejection of claims 3 and 15. Since none of the other prior art of record, whether taken alone or in any combination, discloses or suggests all the features of the claimed invention, Applicants respectfully submit that claims 3 and 15 are allowable.

Claims 6-7, 18-19, 25-26 and 29 stand rejected under 35 U.S.C. § 103(a) as being allegedly unpatentable over U. S. Patent No. 5,652,067 issued to Ito, *et al.* ("Ito") in view of U.S. Patent Publication No. 2003/0170491 issued to Liao, *et al.* ("Liao"). Applicants respectfully traverse this rejection for at least the following reasons.

As noted above, Ito fails to teach or suggest the claimed features of claims 1 and 13. Liao fails to cure the deficiencies of Ito. Claims 6-7 and 18-19 depend from claims 1 and 13 and are allowable at least for this reason.

Accordingly, Applicants respectfully request withdrawal of the 35 U.S.C. § 103(a) rejection of claims 6-7 and 18-19. Since none of the other prior art of record, whether taken alone or in any combination, discloses or suggests all the features of the claimed invention, Applicants respectfully submit that claims 6-7 and 18-19 are allowable.

Claims 25-26 recite *inter alia*:

“...wherein a shadow mask is used to form the electron injecting layer such that the electron injecting layer overlaps the emissive layer without extending over the first and the second ends of the anode layer and the emissive layer” (emphasis added)

As noted above with regard to claim 1, Ito fails to teach or suggest such features.

Accordingly, Applicants respectfully request withdrawal of the 35 U.S.C. § 103(a) rejection of claims 25 and 26. Claim 29 depends from claim 26 and is allowable at least for this reason. Since none of the other prior art of record, whether taken alone or in any combination, discloses or suggests all the features of the claimed invention, Applicants respectfully submit that independent claims 25 and 26, and all the claims that depend therefrom, are allowable

CONCLUSION

Applicants believe that a full and complete response has been made to the pending Office Action and respectfully submit that all of the stated grounds for rejection have been overcome or rendered moot. Accordingly, Applicants respectfully submit that all pending claims are allowable and that the application is in condition for allowance.

Should the Examiner feel that there are any issues outstanding after consideration of this response, the Examiner is invited to contact the Applicants' undersigned representative at the number below to expedite prosecution.

Prompt and favorable consideration of this Reply is respectfully requested.

Respectfully submitted,

/hae-chan park/

Hae-Chan Park
Reg. No. 50,114

Date: October 11, 2006

CUSTOMER NUMBER: 58027

H.C. Park & Associates, PLC
8500 Leesburg Pike
Suite 7500
Vienna, VA 22182
Tel: 703-288-5105
Fax: 703-288-5139
HCP/BYC/kbs